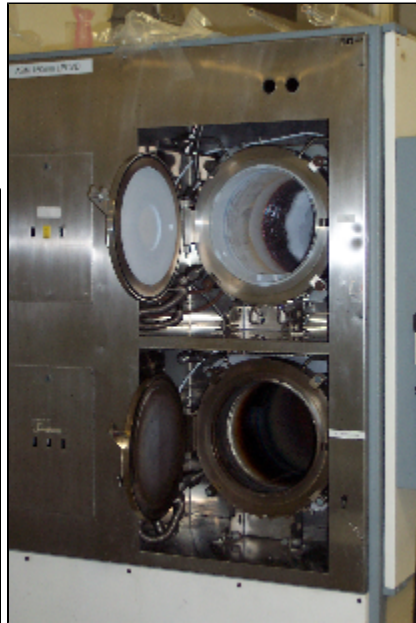


ASM LPCVD Tube 1



Facts

- The ASM LPCVD is a two tube systems capable of depositing polysilicon, silicon nitride and LTO.
 - It is configured for both 4 inch and 6 inch wafers.
 - It uses dedicated quartz boats.
- Tube 1 - LPCVD of low temperature oxide
 - Silane and oxygen are brought into a heated furnace tube at low pressures to react and grow a silicon dioxide film
- Other Tubes
 - ASM LPCVD Tube 2 - LPCVD of Silicon Nitride / Polysilicon

Personnel

- Tool Engineer - Bruce Tolleson
- Process Engineer - Sean O'Brien

Tool & Process Information

- 425C LTO Recipe

Manuals & Users

- ASM LPCVD Manual - Rev M
- ASM LPCVD Certification Checklist